1. **Instructor**

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2. **Course Description**

Learn to design fabrication process flows for advanced micro/nano devices. Develop practical skills with advanced laboratory equipment and instruments. Learn critical skills that are required to work in a cleanroom environment.

3. **Text Book**


Available at UofT bookstore.

Topics include:

- Cleanroom Technology
- Semiconductor Manufacturing
- Photolithography
- Etching Techniques
- E-Beam Lithography

4. **Homework Problems and Exercises**

Homework problems will be assigned weekly. Students are expected to keep up with the homework in order to prepare for tests and exams.

5. **Tutorials**

Tutorials are held weekly. They will cover key homework problems, review key concepts from the lectures, and provide students with a chance to ask individual questions.

6. **Tests**

- There are two tests in this course. The tests are 50 minutes long and will be held during the scheduled lecture hours as follows:
  - Test #1: TBA
  - Test #2: TBA

7. **Labs**

This course is supplemented by 6 laboratory experiments. The purpose of these lab projects is for students to become familiar with advanced laboratory equipment.

- Students work in groups of two.
- You can find a lab partner at the time of the lab information session. Students must have a lab partner in time for the first lab.
- Each student keeps a bound lab book to document their work.
- To receive full marks, students must successfully complete the lab preparation, the lab itself, document their lab results in the lab book, and answer relevant questions posed by the TAs during evaluation. A lab report is to be submitted one week after the lab.
- The Lab handout will be available from the course website.

## 8. Marking Scheme

<table>
<thead>
<tr>
<th>Component</th>
<th>Percentage</th>
</tr>
</thead>
<tbody>
<tr>
<td>Final Exam</td>
<td>55%</td>
</tr>
<tr>
<td>Tests (2)</td>
<td>20%</td>
</tr>
<tr>
<td>Labs (4)</td>
<td>25%</td>
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</tbody>
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